



Nanofabrication with Focused Electron/Ion Beam Induced Processing

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Message from the Guest Editor

This Special Issue aims to provide an in-depth overview on the current status of nanofabrication with focused electron/ion beam induced processing through research papers, short communications, and review articles. Topics include experimental and theoretical contributions on modification and nanofabrication with FEB and FIB-induced processing.

Some examples of its applications are: 1) the material modification by a focused ion beam, such as the tuning of material properties by irradiation, material removal by milling and sputtering, and material addition by focused electron beam in the three dimensions of space; 2) material modification by a focused electron beam, such as the tuning of material properties by irradiation, material removal by etching, and the material addition by focused electron beam in the three dimensions of space; and 3) theoretical approaches of focused electron/ion beam induced processing.

Keywords

3D nanoprinting

Additive nanofabrication and material applications

Subtractive nanofabrication and material applications

Theoretical approaches of processing





Editor-in-Chief

Message from the Editor-in-Chief

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